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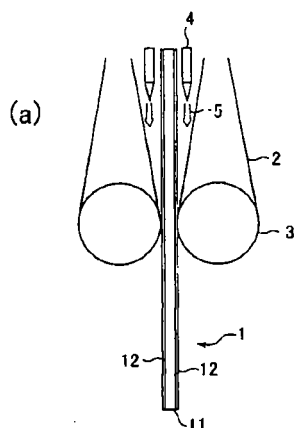
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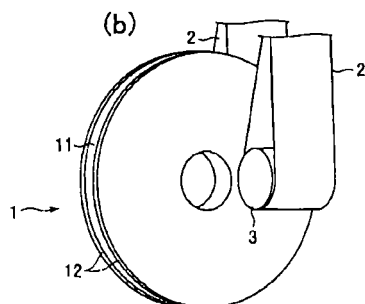
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(54) Title: COMPOSITION FOR TEXTURING PROCESS



(57) Abstract: A composition for use in texturing includes (i) microparticles or powder formed of at least one species selected from the group consisting of diamond, CBN, alumina and silicon carbide; (ii) at least one species selected from the group consisting of C2-C5 polyhydric alcohols, polycondensed products of the alcohols and alkylene glycol monoalkyl ethers represented by formula $R_1O(C_nH_{2n}O)_mH$ (wherein R_1 represents a C1-C4 linear or branched alkyl group, m is an integer of 1 to 3 and n is 2 or 3); and (iii) a C10-C22 fatty acid. When polishing a substrate using the composition, it is possible to form minute texturing lines, remove "polish lines" and "polish scratches" and minimize the mean surface roughness (R_a) of the undercoat layer of the substrate after texturing.



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